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Docket No.: SON-2811
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Kaoru KOIKE

Application No.: 10/526,359

Confirmation No.: 8957

Filed: March 2, 2005

Art Unit: 2856

For: ALIGNMENT METHOD, ALIGNMENT
SUBSTRATE, PRODUCTION METHOD OF
ALIGNMENT SUBSTRATE, EXPOSURE
METHOD, EXPOSURE APPARATUS AND
PRODUCTION METHOD OF MASK

Examiner: Stacy Whitmore

SECOND INFORMATION DISCLOSURE STATEMENT

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450
Dear Sir:

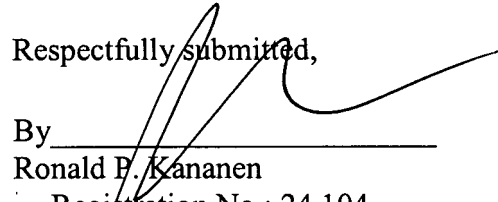
Further to the IDS at filing, the Applicant, through its representatives and attorneys, hereby brings to the examiner the information that one of the documents submitted at filing with the ISR was also cited in an Action of July 3, 2007 in Japan in connection with the corresponding Japanese priority application. A copy of the document, its English language abstract, and the Japanese Action accompany this submission. No English language translation of the Japanese Action is readily available. No machine translation of the cited JP Publication is readily available.

Please take this document into account in the initial examination of this application and make its consideration of record, even if somewhat duplicative of a document previously presented.

No fee is believed necessary in that this submission is made prior to a first action on the merits of this application.

Dated: October 4, 2007

Respectfully submitted,

By 

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